

10/578683

IAP12 Rec'd PCT/PTO 09 MAY 2006

Customer No. 22,852
Attorney Docket No. 05823.0283

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Hai Won LEE et al.)
) Group Art Unit:
Application No.: Not Yet Assigned)
) Examiner:
Filed: May 9, 2006)
)
For: FABRICATION METHOD OF)
EXTREME ULTRAVIOLET)
RADIATION MASK MIRROR)
USING ATOMIC FORCE)
MICROSCOPE LITHOGRAPHY)

U.S. National Phase of International PCT Application No. PCT/KR2004/001363

**MAIL STOP PCT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450**

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§1.56 and 1.97(b), applicants bring to the Examiner's attention the documents listed on attached Form PTO/SB/08 and cited in the enclosed international search report. Copies of the listed foreign patent document and listed non patent literature documents are attached. Applicants respectfully request that the Examiner consider the documents listed on attached Form PTO/SB/08 and indicate that they were considered by making an appropriate notation on this form.

This Information Disclosure Statement is being filed with the above-referenced application.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such documents. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: May 9, 2006

By: 

Ernest F. Chapman
Reg. No. 25,961

Enclosures
EFC/FPD/gah

IDS Form PTO/SB/08: Substitute for form 1449A/PTO

Complete if known **10/1578683****INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use as many sheets as necessary)

Sheet

1

of

1

Application Number

Filing Date

May 9, 2006

First Named Inventor

Hai Won LEE

Art Unit

Examiner Name

Attorney Docket Number

05823.0283

U.S. PATENTS AND PUBLISHED U.S. PATENT APPLICATIONS

Examiner Initials	Cite No. ¹	Document Number	Issue or Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
		US-6,110,607	09-29-2000	Montcalm et al.	
		US-6,229,652 B1	05-08-2001	Bajt et al.	
		US-6,228,512 B1	05-08-2001	Bajt et al.	
		US-4,329,410	05-11-1982	Buckley	
		US-6,338,990 B1	01-15-2002	Yanai et al.	
		US-			

Note: Copies of the U.S. Patent Documents are not Required in IDS filed after October 21, 2004**FOREIGN PATENT DOCUMENTS**

Examiner Initials	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation ⁶
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				

NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Translation ⁶
		RYU; "METHOD FOR MANUFACTURING A SEMICONDUCTOR DEVICE"; Korean Patent Abstracts of KR 1020000073498 A, May 12, 2000.	
		MATSUO et al.; "MANUFACTURE OF MASK FOR EXPOSURE TO X-RAY AND BLANK USED THEREWITH"; Patent Abstracts of Japan of JP 05-283323, October 29, 1993	
		SUNDERMANN et al.; "NANOPATTERNING OF Au ABSORBER FILMS ON Mo/Si EUV MULTILAYER MIRRORS BY STM LITHOGRAPHY IN SELF-ASSEMBLED MONOLAYERS"; Surface Science, Vol. 454- 456, pages 1104-1109, (2000)	

Examiner
SignatureDate
Considered

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.